

Effects of Octahedral Ni²⁺ on Structural and Transport Properties of Ni_xFe_{3-x}O₄ Thin Films

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Polycrystalline Ni_xFe_{3-x}O₄ thin films prepared by using a sol-gel process exhibited phase-pure spinel ($Fd\bar{3}m$) structure for the Ni composition up to $x = 1.0$. X-ray photoemission spectroscopy (XPS) and Raman spectroscopy investigations revealed that Ni ions mostly have valence of +2 and occupy the octahedral sites of the cationic sublattice. The Ni_xFe_{3-x}O₄ films exhibited higher electrical resistivity than that of Fe₃O₄ below 300 K. The increase in the resistivity is primarily ascribed to decrease in Fe²⁺-Fe³⁺ polaronic hopping rate in the octahedral sites due to the increase in the octahedral Ni²⁺ population.

Keywords : magnetite, ferrite thin film, electrical resistivity, polaron, sol-gel

1. Introduction

The iron-oxide magnetite (Fe₃O₄) has been subject to a large number of theoretical and experimental studies due to its intriguing physical properties as well as technical applications such as power transformer, magnetic recording, magnetic refrigeration, and ferro-fluids [1-3]. The structural and magnetic properties of magnetite related to such applications can be tuned via substitution of the tetrahedral (A) or octahedral (B) cations by foreign metallic ions with little distortion of the spinel lattice. The ferrimagnetism of inverse spinel Fe₃O₄ below 860 K has been explained in terms of the antiferromagnetic spin alignment between Fe³⁺(A) and Fe³⁺(B) ions via the super-exchange interaction, while Fe²⁺(B) aligns parallel to Fe³⁺(B) via the double-exchange interaction [4]. With the magnetic moment of high-spin Fe³⁺(A) ion being opposite to those of Fe³⁺(B) and Fe²⁺(B) ions, Fe₃O₄ can exhibit a net magnetic moment of $\sim 4 \mu_B$ per formula unit ($= 500 \text{ emu/cm}^3$).

Despite an oxide material, Fe₃O₄ is known to have high electrical conductivity, $\sim 10^2 \Omega^{-1}\text{cm}^{-1}$ at temperatures near 300 K, which can be explained in terms of the polaronic electron hopping between the octahedral cations [5]. When

Ni ions substitute the cationic sublattice of magnetite, the resultant Ni_xFe_{3-x}O₄ compounds disclosed a gradual decrease of magnetization with decreasing Ni composition [6]. In this work, the temperature dependence of electrical resistivity of Ni_xFe_{3-x}O₄ thin films have been measured for the Ni composition up to $x = 1.0$. Although majority of research on ferrites tend to be populated on powder samples, film samples are more advantageous for accurate measurements of the inherent properties of granular oxides such as electrical resistivity, optical absorption, and photoemission.

The structural properties of the present sol-gel prepared Ni_xFe_{3-x}O₄ thin films were investigated by X-ray diffraction (XRD) and Raman spectroscopy. The ionic valences of Fe and Ni ions in Ni_xFe_{3-x}O₄ were investigated by X-ray photoemission spectroscopy (XPS). The electrical resistivity of the Ni_xFe_{3-x}O₄ samples was measured at varying temperature in order to investigate the variation in polaronic conductivity with Ni doping.

2. Experimental

The present Ni_xFe_{3-x}O₄ films were fabricated by using a sol-gel process wherein the precursor solution was prepared by dissolving Fe(NO₃)₃·9H₂O and Ni(CH₃CO₂)₂·4H₂O powders together in 2-methoxyethanol at 160 °C. The substrate, α -Al₂O₃(0001), was spin-coated by the precursor solution at 3000 rpm for 20 s and then heated at 300 °C

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for 4 min. This process was repeated for increasing the film thickness. For the present $\text{Ni}_x\text{Fe}_{3-x}\text{O}_4$ films with phase purity, post-annealing was performed in evacuated ($\sim 10^{-3}$ Torr) quartz tube at 800 °C for 4 h.

The thickness of the magnetic films estimated by using scanning electron microscopy was in the 0.6–0.8 μm range. The crystalline structure of the samples was monitored by using XRD ($\text{Cu } K_\alpha$ line) in the grazing-incidence geometry with fixed X-ray incidence angle of 4°. XPS measurements were performed using the $\text{Al } K_\alpha$ line in order to find preferred valence of Ni and Fe ions in the oxides. Raman spectra of the specimens were measured using an Ar-ion laser (wavelength = 514 nm) at room temperature. Temperature-dependent DC electrical resistivity measurements were performed on bar-shaped (1 mm wide and 10 mm long) samples in the 100–300 K range by using a ^4He cryostat (PPMS-9, Quantum DesignTM, San Diego, CA, USA). At each temperature (T) step ($\Delta T = 1$ K), the measurement was performed under a current supply of 1 mA after the temperature had stabilized.

3. Results and Discussion

The XRD patterns of the sol-gel prepared polycrystalline $\text{Ni}_x\text{Fe}_{3-x}\text{O}_4$ ($x \leq 1.0$) films are exhibited in Fig. 1. All the diffraction peaks could be indexed based on a spinel phase (cubic space group $Fd\bar{3}m$; JCPDS 88-0866) regardless of the Ni composition (x). The XRD peaks of the $\text{Ni}_x\text{Fe}_{3-x}\text{O}_4$ samples shift to larger angles with increasing x as shown by a dashed line near the (440) peak, indicating a gradual decrease of the lattice parameter of $\text{Ni}_x\text{Fe}_{3-x}\text{O}_4$. For the Fe_3O_4 film, the calculated cubic lattice parameter is 0.8385 nm, which is in agreement with a bulk lattice parameter (0.8385 nm in JCPDS 88-0866). The lattice

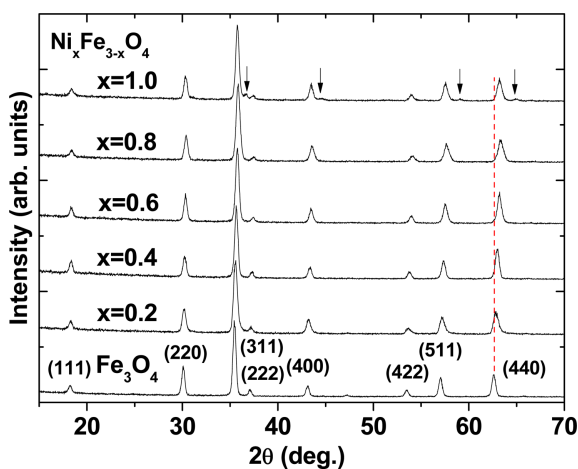


Fig. 1. (Color online) X-ray diffraction patterns of polycrystalline $\text{Ni}_x\text{Fe}_{3-x}\text{O}_4$ films.

parameters of the $\text{Ni}_x\text{Fe}_{3-x}\text{O}_4$ films are 0.8370, 0.8347, 0.8317, and 0.8299 nm for $x = 0.2, 0.4, 0.6,$ and $0.8,$ respectively. However, for $x = 1.0$, new peaks appear near (311), (400), (511), and (440) peaks as marked by arrows in Fig. 1. It can be understood in terms of a tetragonal distortion of the unit cell at large Ni compositions.

In Fig. 2(a), the Ni $2p$ -electron binding-energy (BE) spectra of the $\text{Ni}_x\text{Fe}_{3-x}\text{O}_4$ samples obtained by XPS measurements are exhibited. The emission peaks near 854 and 872 eV (marked by arrows) are identified as the spin-orbit-split $2p_{3/2}$ and $2p_{1/2}$ peaks, respectively, from ionic Ni with valence of +2. The peak near 861 eV (marked by asterisk) is identified as a major satellite to the $2p_{3/2}$ emission from octahedral Ni^{2+} ions [7, 8]. Thus, the Ni $2p$ XPS spectra indicate dominance of octahedral Ni^{2+} ions in the $\text{Ni}_x\text{Fe}_{3-x}\text{O}_4$ samples. In Fig. 2(b), the Fe $2p$ -electron BE spectra of the $\text{Ni}_x\text{Fe}_{3-x}\text{O}_4$ samples show that the main $2p_{3/2}$ peak can be resolved by two contributions, Fe^{2+} near 709 eV and Fe^{3+} near 711 eV as marked by arrows. The photoelectron spectral shapes for the present $\text{Ni}_x\text{Fe}_{3-x}\text{O}_4$ samples are well distinguishable from those for iron oxides

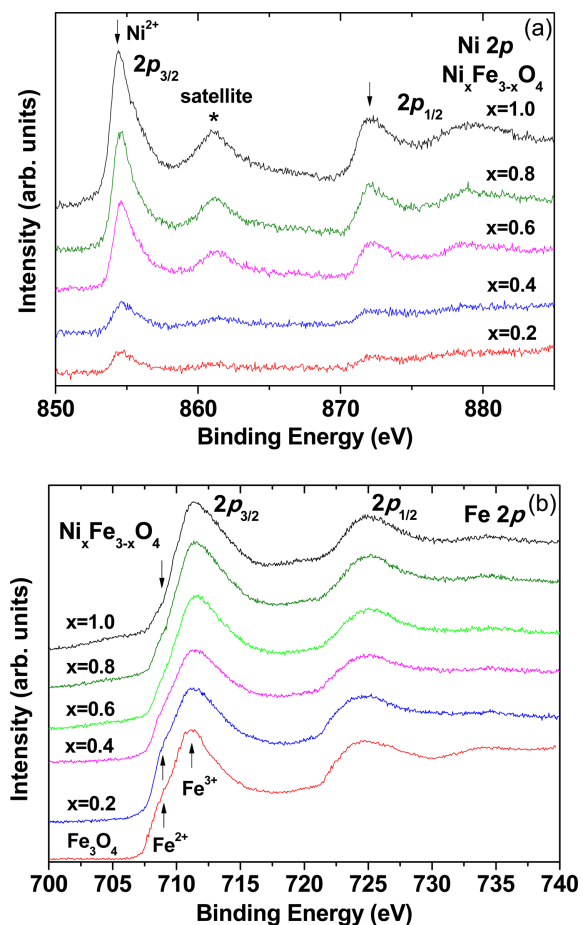


Fig. 2. (Color online) X-ray photoemission spectra of (a) Ni $2p$ and (b) Fe $2p$ electrons of polycrystalline $\text{Ni}_x\text{Fe}_{3-x}\text{O}_4$ films.

containing Fe³⁺ ions only [9, 10]. For the Ni_xFe_{3-x}O₄ samples, the Fe²⁺ strength is seen to become weaker with increasing x compared to that of Fe₃O₄, suggesting a decrease in the octahedral Fe²⁺ concentration caused by the Ni²⁺ substitution. The octahedral preference of the Ni ions has been reported in a number of study on spinel oxides [11, 12]. The decrease of the lattice parameter for Ni_xFe_{3-x}O₄ with increasing x as indicated by the XRD data (Fig. 1) can be explained in terms of the smaller ionic radius of high-spin Ni²⁺ ion (0.069 nm) than that of high-spin Fe²⁺ ion (0.078 nm) in the octahedral site.

In Fig. 3, the Raman spectra of the nickel-ferrite samples are exhibited in comparison with that of Fe₃O₄. The Raman spectrum of the Fe₃O₄ sample exhibits a prominent peak near 667 cm⁻¹, which is assigned to the A_{1g} phonon mode associated with symmetric stretching of oxygen in the tetrahedral (AO₄) sites [13, 14]. For the Ni_xFe_{3-x}O₄ samples, the corresponding Raman peak shifts to the higher energies with increasing x (704 cm⁻¹ for x = 1.0) compared to that of Fe₃O₄ as denoted by arrows. It is seen that the A_{1g} peak maintains similar lineshape for all the samples, implying that the tetrahedral sites are hardly occupied by foreign (Ni²⁺) ions, thus, supporting the octahedral preference of the Ni²⁺ ions. It is also seen that the Raman peak near 540 cm⁻¹ for Fe₃O₄, being ascribed to one of the three T_{2g} modes associated with asymmetric stretching of oxygen in the AO₄ sites, gets stronger and gradually shifts to higher energies with increasing x (580 cm⁻¹ for x = 1.0) as in the A_{1g} mode. Such high-energy shift of the two phonon modes for Ni_xFe_{3-x}O₄ is interpreted as due to the increase of the A-O bond strength [15] caused by the decrease of the lattice parameter of the nickel-ferrites compared to that of Fe₃O₄. A Raman peak appearing near 330 cm⁻¹ at large Ni compositions (x ≥ 0.6) is ascribed to

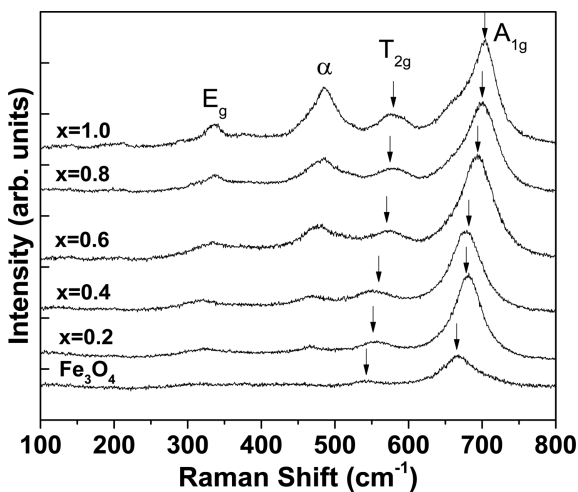


Fig. 3. Raman shifts of polycrystalline Ni_xFe_{3-x}O₄ films.

the E_g mode associated with symmetric bending of the tetrahedral O²⁻ ions. There is another Raman peak prominent at large Ni compositions near 480 cm⁻¹ (denoted as α). It was interpreted as due to excitation of magnons [15, 16].

In Fig. 4(a), the electrical resistivity (ρ) data of the Ni_xFe_{3-x}O₄ films are exhibited. All the specimens show decreasing ρ with increasing T that can be observed for usual non-metallic materials. The electrically insulating α-Al₂O₃(0001) substrate seldom affect the measurement of ρ. It is also seen that ρ of the Ni_xFe_{3-x}O₄ films gets larger with increasing x at all temperatures. At T = 300 K, ρ is as low as 1.6 × 10⁻¹ Ω·cm for Fe₃O₄, while it is 1.4 × 10¹ Ω·cm for x = 1.0, thus, being increased by a factor of ~10². The increase in the resistivity of the Ni_xFe_{3-x}O₄ samples compared to that of Fe₃O₄ can be understood in terms of the decrease of thermally-activated d-electron hopping rate between Fe²⁺(d⁶) and Fe³⁺(d⁵) ions in the

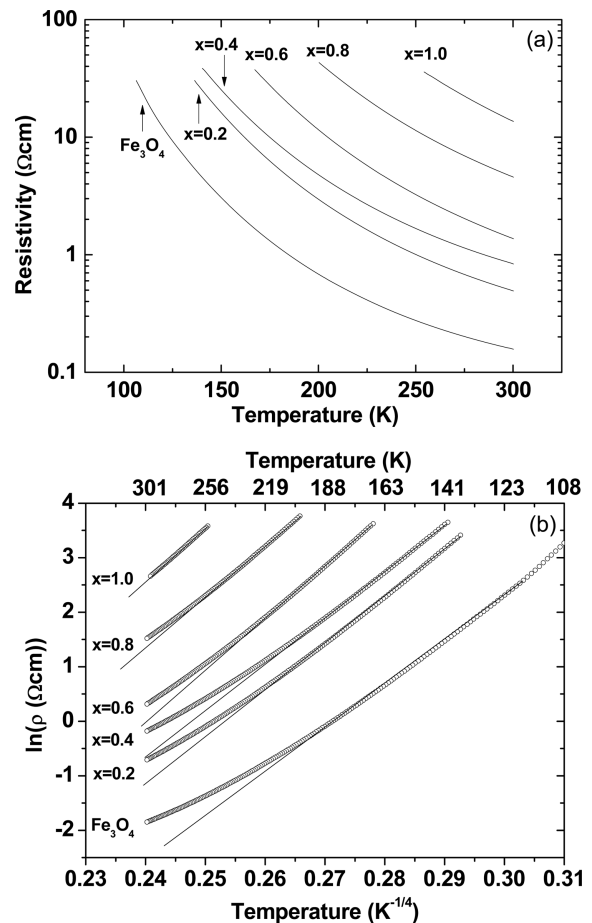


Fig. 4. (a) Temperature dependence of DC electrical resistivity ρ of Ni_xFe_{3-x}O₄ films. (b) Dependence of ln(ρ) on T^{-1/4}. The experimental data are denoted as open circles. The straight lines drawn along with the experimental data are obtained by least-squares fittings on linear region of the data points.

octahedral sites of the spinel lattice [11, 17]. Such electron-hopping conduction in ionic crystals has been theoretically explained in terms of polaron, a virtual particle composed of an electron and surrounding phonons [18]. In inverse-spinel Fe_3O_4 where the octahedral sites are occupied by equal quantity of Fe^{2+} donors and Fe^{3+} acceptors, the donor-acceptor pairs for the polaronic transport exist in abundance. The decrease in the octahedral Fe^{2+} quantity through Ni^{2+} substitution in $\text{Ni}_x\text{Fe}_{3-x}\text{O}_4$ leads to a decrease in $\text{Fe}^{2+}\text{-Fe}^{3+}$ pairs, resulting in the decrease in electrical conductivity.

Considering the polaron as originating from Coulombic electron-phonon interaction, the decreasing resistivity with increasing T can be explained in terms of the increase in the phonon population and the resultant increase in the polaronic $\text{Fe}^{2+}\text{-Fe}^{3+}$ hopping probability. The temperature dependence of electrical properties caused by polaronic hopping can be described as

$$\ln\left(\frac{\rho}{\rho_0}\right) = \left(\frac{T_0}{T}\right)^q$$

wherein the exponent q is variable as $q = 1$ for nearest-neighbor hopping (NNH) and $q = 1/4$ for variable-range hopping (VRH), and ρ_0 and T_0 are constants [18, 19]. Thus, in Fig. 4(b), the plots of $\ln(\rho)$ of the $\text{Ni}_x\text{Fe}_{3-x}\text{O}_4$ films on $T^{-1/4}$ are exhibited. The $\ln(\rho)$ data are seen to vary in quite linear manner with $T^{-1/4}$ at low temperatures. The linear part of the $\ln(\rho)$ vs. $T^{-1/4}$ plot in the low temperature region was least-squares fitted as denoted by straight line in in Fig. 4(b). The $x = 0.2, 0.4,$ and 0.6 samples show good linearity up to ~ 220 K. On the other hand, such linear behavior was not observed for the $\ln(\rho)$ vs. T^{-1} relation of the samples in the same temperature range. Thus, the analysis on the temperature dependence of $\ln(\rho)$ implies that the polaronic transport of $\text{Fe } d$ electrons in $\text{Ni}_x\text{Fe}_{3-x}\text{O}_4$ is better explained by the VRH model than the NNH model at low temperatures.

4. Conclusions

Polycrystalline $\text{Ni}_x\text{Fe}_{3-x}\text{O}_4$ ($x \leq 1.0$) thin films prepared by sol-gel process exhibit phase purity and decrease of lattice parameter with increasing Ni composition. XPS and Raman investigations reveal that the Ni ions in $\text{Ni}_x\text{Fe}_{3-x}\text{O}_4$ have valence of +2 and occupy octahedral sites mostly. The electrical resistivity data for the $\text{Ni}_x\text{Fe}_{3-x}\text{O}_4$ films exhibit $T^{-1/4}$ dependence at low temperatures (< 220 K), implying VRH-type polaronic transport. The decrease in the octahedral Fe^{2+} population and the resultant

decrease in the $\text{Fe}^{2+}\text{-Fe}^{3+}$ hopping probability by the Ni doping is ascribed to the main reason for the gradual increase in the resistivity with increasing x .

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References

- [1] A. Goldman, *Modern Ferrite Technology*, Springer, New York (2006).
- [2] U. B. Gawas, V. M. S. Verenkar, S. R. Barman, S. S. Meena, and P. Bhatt, *J. Alloys Comp.* **555**, 225 (2013).
- [3] Q. Liu, Z. Zi, M. Zhang, A. Pang, J. Dai, and Y. Sun, *J. Alloys Comp.* **561**, 65 (2013).
- [4] M. Ishikawa, H. Tanaka, and T. Kawai, *Appl. Phys. Lett.* **86**, 222504 (2005).
- [5] S. B. Ogale, K. Ghosh, R. P. Sharma, R. L. Greene, R. Ramesh, and T. Venkatesan, *Phys. Rev. B* **57**, 7823 (1998).
- [6] K. J. Kim, M. H. Kim, and C. S. Kim, *J. Magn.* **19**, 111 (2014).
- [7] S. Altieri, L. H. Tjeng, A. Tanaka, and G. A. Sawatzky, *Phys. Rev. B* **61**, 13403 (2000).
- [8] S. Ivanova, E. Zhecheva, R. Stoyanova, D. Nihtianova, S. Wegner, P. Tzvetkova, and S. Simova, *J. Phys. Chem. C* **115**, 25170 (2011).
- [9] T. Fujii, F. M. F. de Groot, G. A. Sawatzky, F. C. Voogt, T. Hibma, and K. Okada, *Phys. Rev. B* **59**, 3195 (1999).
- [10] K. J. Kim, J. H. Lee, and C. S. Kim, *J. Kor. Phys. Soc.* **61**, 1274 (2012).
- [11] A. K. Singh, T. C. Goel, and R. G. Mendiratta, *Solid State Commun.* **125**, 121 (2003).
- [12] M. Sertkol, Y. Koseoglu, A. Baykal, H. Kavas, and A. C. Basaran, *J. Magn. Mater.* **321**, 157 (2009).
- [13] Z. Wang, R. T. Downs, V. Pischcheda, R. Shetty, S. K. Saxena, C. S. Zha, Y. S. Zhao, D. Schiferl, and A. Waszkowska, *Phys. Rev. B* **68**, 094101 (2003).
- [14] O. N. Shebanova and P. Lazor, *J. Solid State Chem.* **174**, 424 (2003).
- [15] R. Gupta, A. K. Sood, P. Metcalf, and J. M. Honig, *Phys. Rev. B* **65**, 104430 (2002).
- [16] L. Degiorgi, I. Blatter-Morke, and P. Wachter, *Phys. Rev. B* **35**, 5421 (1987).
- [17] P. P. Hankare, K. R. Sanadi, K. M. Garadkar, D. R. Patil, and I. S. Mulla, *J. Alloys Comp.* **553**, 383 (2013).
- [18] R. Schmidt, A. Basu, and A. W. Brinkman, *Phys. Rev. B* **72**, 115101 (2005).
- [19] A. Karmakar, S. Majumdar, and S. Giri, *Phys. Rev. B* **79**, 094406 (2009).